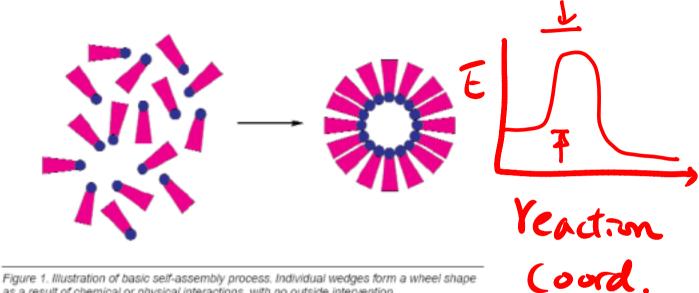
Chapter 10

Self-Assembly and Catalysis

10.1.1 Self-Assembly



as a result of chemical or physical interactions, with no outside intervention.

Traditional synthesis: kinetic control

Self-assembly: thermodynamic control

Covalent bond: ~100 Kcal/mole

Hydrogen bond: ~10 Kcal/mole

Van der Waals : ~1 Kcal/mole

Thermal energy: 3/2 kT at 300K

=> 0.45 Kcal/mole

10.1.1 Self-Assembly

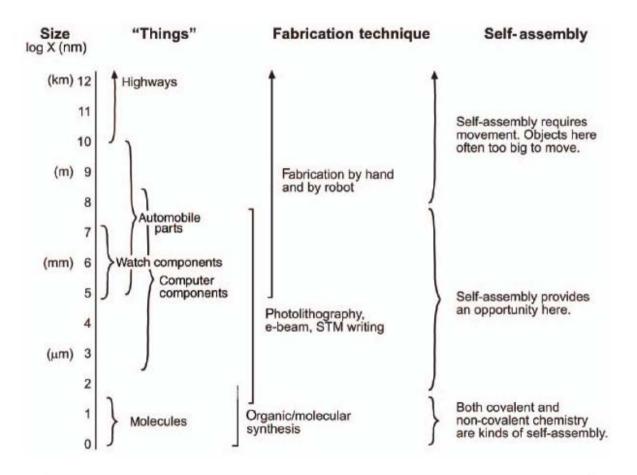


Figure 1. Chart illustrating the general scheme of "making things" at size scales ranging from nanometers to kilometers, and the possible niches for application of mesoscale self-assembly.

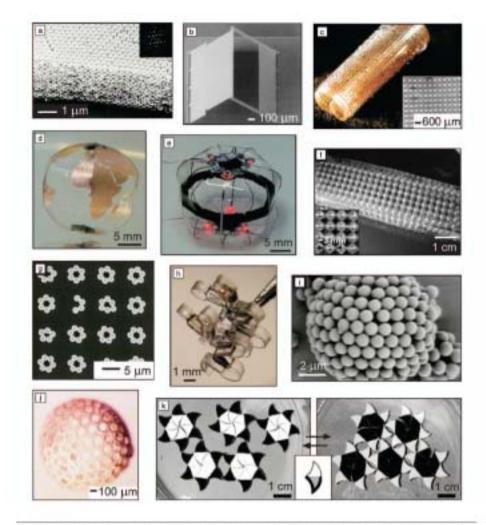
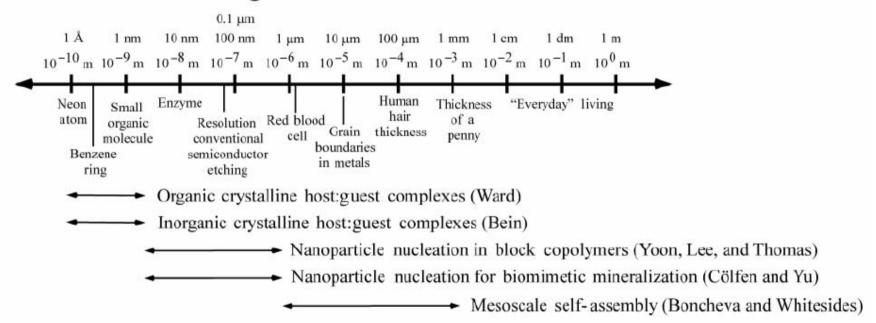


Figure 2. Examples of self-assembled mesoscale structures, (a) A hallow TiO₂ colloidal crystal. The inset shows Fourier deviation of 40 µm × 40 µm inglion in the (TIT) parts of the erystal. (Reported in part with permittation them interferone 23.) (a) An approved in interconnect from a planuar precurator by surface fertical parts with permitted in part with permittation from Redemone 36.) (c) A large-area array of alloos degreests self-assembled on a feedber, nonplanuar support. The inset brown a detail of the structure, (Reported with permittation from Redemone 27.) (a) An eastitument of the self-assembled from a fat, 20 projection of the Earth.** (Integer, M. Bononesia.) (e) A senf-assembled hallow self-assembled from a fat, 20 projection of the Earth.** (Integer, M. Bononesia.) (e) A senf-assembled ample cubic allowed in part with permittation from Redemone 38.) (g) An array of ring-chapsel aggregates of polystyrene heads. (Registed in part with permittation from Redemone 30.) (i) A 20 releast shows est-assembled from a competed establishment from Redemone 31.) (i) A port tollow cappair protection of the polystyrene establishment from Redemone 31.) (ii) A port tollow cappair protection from Redemone 31.) (ii) A port tollow cappair (interest assembled on a drap of characteristic and an appearance of the polystyrene in an aqueous alternative polystyrene for the part with permitted in part with permitted in part with permitted in the Redemone 33.) (ii) Sent different ratched write permitted in part with permitted in part with permitted in the Redemone 33.) (ii) Sent different ratched write permitted in part with permitted in part with permitted in part with permitted in the Redemone 33.) (iii) Redemone 33.) (iv) Sent different ratched which permitted in part with permitted in part wi

10.1.1 Self-Assembly

Length-Scale Continuum



10.1.2 Semiconductor island

$$\frac{dn_1}{dt} = (R_{ads} + R_{det} + 2R_1) - (R_{evap} + R_{cap} + 2R_1')$$

$$g = (g_{sur-vac}(1-e)) + (g_{sur-lay} + g_{lay-vac})e \quad \text{Surface}$$

$$f = \frac{ia_f - a_s i}{a_s}$$

$$G = (g_{sur-vac}(1-e)) + (g_{sur-lay} + g_{lay-vac})e \quad \text{Surface}$$

$$G = (g_{sur-vac}(1-e)) + (g_{sur-lay} + g_{lay-vac})e \quad \text{Surface}$$

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$$G = (g_{sur-vac}(1-e)) + (g_{sur-lay} + g_{lay-vac})e \quad \text{Surface}$$

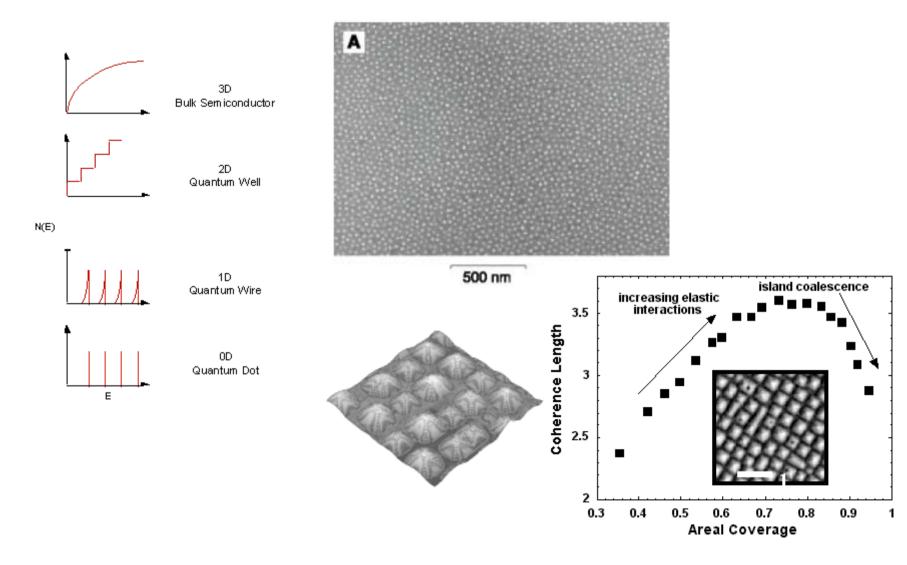
$$G = (g_{sur-vac}(1-e)) + (g_{sur-lay} + g_{lay-vac})e \quad \text{Surface}$$

$$G = (g_{sur-vac}(1-e)) + (g_{sur-lay} + g_{lay-vac})e \quad \text{Surface}$$

$$G = (g_{sur-vac}(1-e)) + (g_{sur-lay} + g_{lay-vac})e \quad \text{Surface}$$

$$G = (g_{sur-vac}(1-e)) + (g_{sur-lay} + g_{lay-vac})e \quad \text{Surface}$$

10.1.2 Semiconductor island



10.1.3 Self assemble monolayer

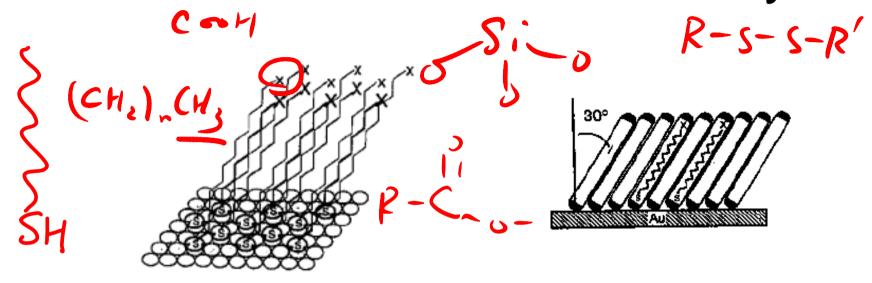
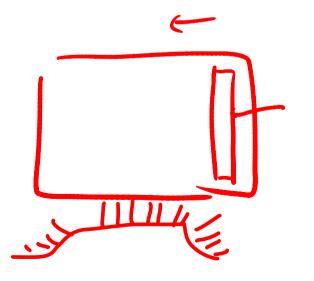


Figure 10.3. Illustration of the self-assembly of a monolayer of *n*-alkanethiolates on gold. The terminal sulphur resides in the hollow between three close-packed gold atoms, as shown in Fig. 10.2. The terminal groups labeled by X represent methyl. (From J. I. Wilher

M + 5-5 -> 5-M-5

 $CH_{3}(CH_{2})_{n}SH + Au_{m} \Rightarrow CH_{3}(CH_{2})_{n}S^{-}(Au_{3}^{+}) \cdot Au_{m-3} + \frac{1}{2}H_{2}$ $Au_{n}A_{3} \cdot P_{4} \cdot N \cdot Cu_{n}G_{4}$ $S: C_{1}G_{4}$



10.2 Catalysis

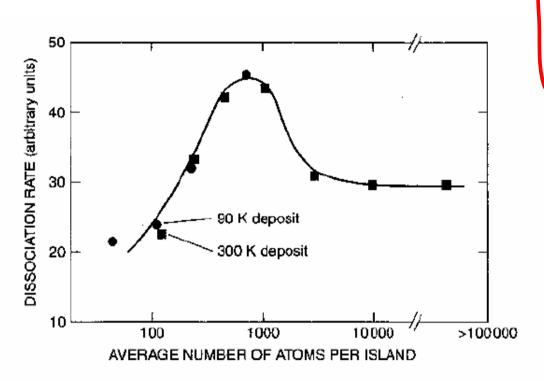


Figure 10.5. Effect of catalytic particle size on the dissociation rate of carbon monoxide. Rhodium aggregates of various sizes, characterized by the number of Rh atoms per aggregate, were deposited on alumina (Al_2O_3) films. The rhodium was given a saturation carbon monoxide (CO) coverage, then the material was heated from 90 to 500 K (circles), or from 300 to 500 K (squares), and the amount of atomic carbon formed on the rhodium provided a measure of the

10.2.2 Surface area

Unix :
$$m^{2}/q$$

$$S = \frac{\alpha reu}{A \cdot P \cdot V} = \frac{u \cdot r^{2}}{P \cdot \frac{u}{3} \cdot r^{3}} = \frac{3}{P \cdot P}$$

$$V = \frac{u}{3} \cdot T \cdot Y^{3} = \frac{6}{P \cdot O}$$

$$A = u \cdot T \cdot Y^{2} = \frac{6}{(3c_{m}^{2}) - nm}$$

$$= \frac{6 \times 10^{3}}{P \cdot O(nm)}$$

10.2.2 Surface area

Langmuir Isotherm

Langmuir suggests that adsorption takes place through this mechanism: $A_g + S = AS$, where A is a gas molecule and S is an adsorption site.

The direct and inverse rate constants are k and k_{-1} . If we define surface coverage, , as the fraction of the adsorption sites which are occupied, in the equilibrium we have

$$K = \frac{k}{k_{-1}} = \frac{\theta}{(1-\theta)P}$$
 or $\theta = \frac{KP}{1+KP}$

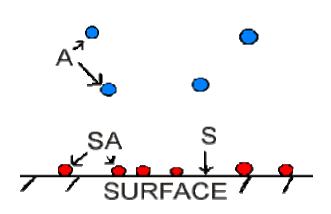
BET Isotherm

Often molecules do form multilayers, that is, some are adsorbed on already adsorbed molecules and the Langmuir isotherm is not valid. In 1938 Stephan Brunauer, Paul Emmett and Edward Teller developed an isotherm that takes into account that possibility. The proposed mechanism is now:

$$Ag + S = AS$$

 $Ag + AS = A2S$
 $Ag + A2S = A3S$ and so on

Langmuir Isotherm



$$\frac{d\theta}{dt} = k_a p N(1 - \theta)$$

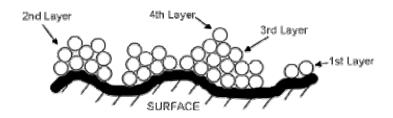
$$\frac{d\theta}{dt} = -k_d N\theta$$

$$S + A = SA$$

$$K = \frac{[SA]}{[S][A]}$$

$$b = \frac{\theta}{(1-\theta)P}$$

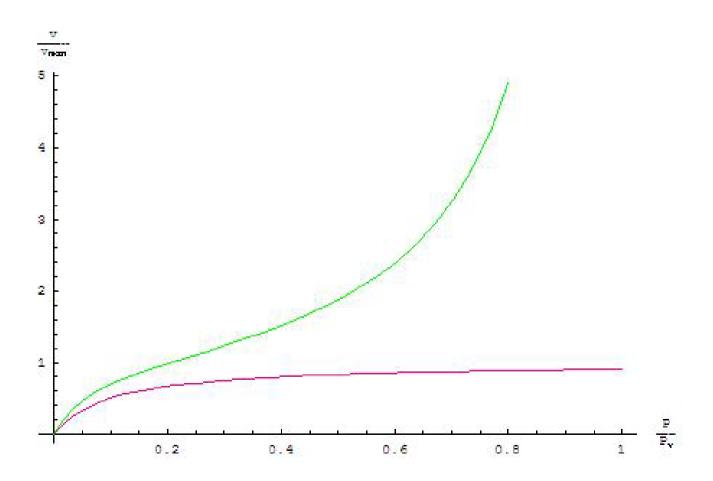
BET Isotherm



$$v = {v_m cx \over (1-x)(1+(c-1)x)}$$

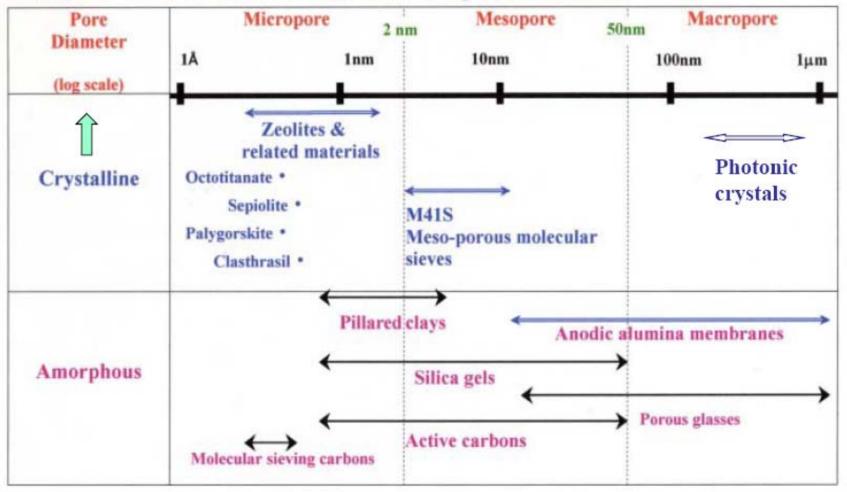
$$\frac{x}{v(1-x)} = \frac{1}{v_{m}c} + \frac{x(c-1)}{v_{m}c}$$

Langmuir and BET Isotherm



10.2.3 Porous materials

Scheme 1. Pore size distribution of various porous materials.



10.2.3 Porous materials

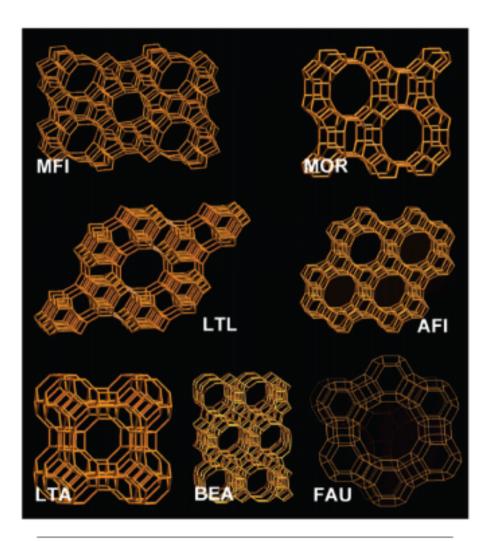


Figure 1. Structures of the seven zeolite types discussed in this article. The three-letter labels are structure codes. (From Reference 4.)

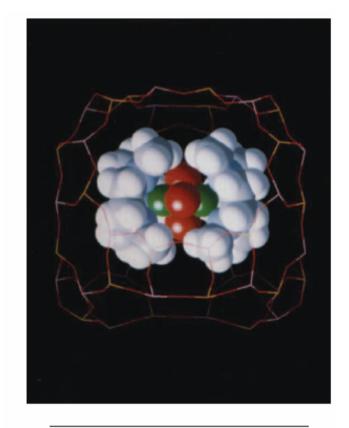


Figure 2. Formation of $[(L'Mn^{III}-(X)_3-Mn^{IV}(L')]^{n+}$ (n = 1-4) from manganese(1,4,7-trimethyl-1,4,7-triazacyclononane)]²⁺ ($[(Mn(L')]^{2+})$ upon reaction with H_2O_2 in the cages of zeolite Y (X = O^{2-} , OH^-). L' is (1,4,7-trimethyl-1,4,7-triazacyclononane). (From Reference 12.)

Zeolites

Zeolites are microporous crystalline solids with well-defined structures. Generally they contain silicon, aluminium and oxygen in their framework and cations, water and/or other molecules wthin their pores. Many occur naturally as minerals, and are extensively mined in many parts of the world. Others are synthetic, and are made commercially for specific uses, or produced by research scientists trying to understand more about their chemistry.



10.2.3 Porous materials

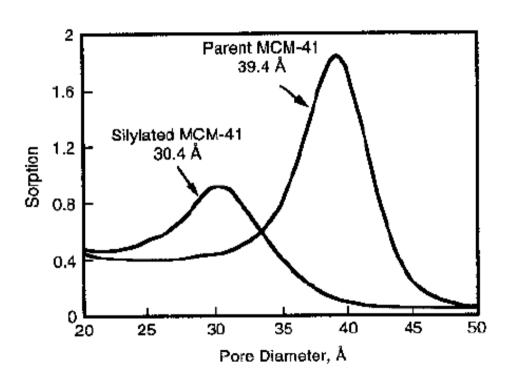


Figure 10.8 Distribution of pore diameters in two molecular sieves with mean pore diameters of 3.04 and 3.94 nm, determined by the physisorption of argon gas. [From J. S. Beck, J. C. Vartuli, W. J. Roth, M. E. Leonowicz, C. T. Kresge, K. D. Schmitt, C. T.-W. Chu, D. H. Olson, E. W. Sheppard, S. B. McCullen, J. B. Higgins, and J. L. Schenkler, *J. Am. Chem. Soc.* 114,

Acidic Site D proton donne

Figure 10.13. Configuration of sulphate group on the surface of a zirconia-sulfate catalyst, showing the Lewis acid site Zr⁻ at the left, and the Brønsted acid site H⁺ at the right. [From



10.2.4 Clays

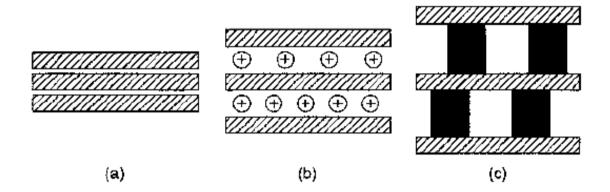
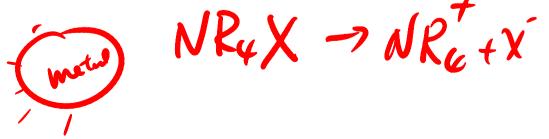


Figure 10.15. Saponite clay layers shown (a) before adsorption (b) after adsorption of cations.

10.2.5 Colloids

organosal: colloid in organiz lique hydrosol



10.2.5 Colloids

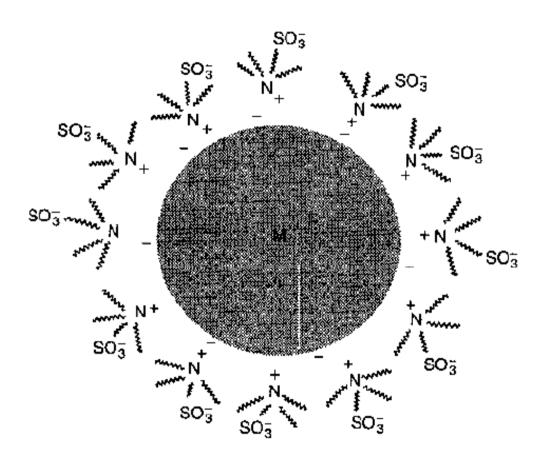


Figure 10.23. Metallic colloidal particle stabilized by sulfobetaine compounds related to NR_4X , but with an SO_3^- group at the end of one of the alkyl chains R. [From H. Bönnemann and W. Brijoux, in Moser (1996), Chapter 7, p. 174.]

Chapter 11

Organic Compounds and Polymers

11.2 Polymer

monomer

11.2.2 Size of polymers

$$V(cw^3) = \frac{Mw}{P} \left(\frac{g}{male} \rightarrow \# 6x^3\right)$$

$$\frac{3}{male} \rightarrow \# 6x^3$$

$$V=d^3=1.66\times 10^{-3}\frac{M_m}{p}$$

$$\Rightarrow$$
 $d = 0.118 (\frac{Mm}{pm})^{3}$

Homework: relationship for spherical polymer

11.4.1 Conducting Polymers

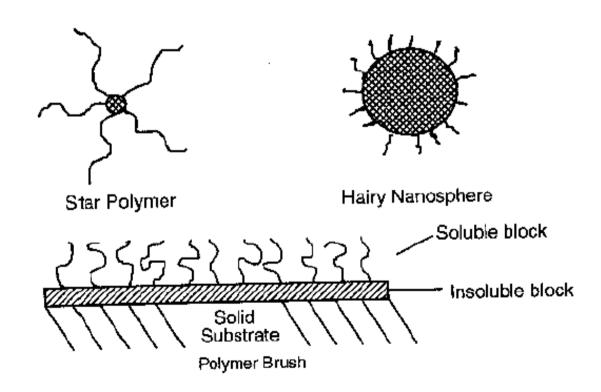
$$-(=(-=)) + (=(-))$$

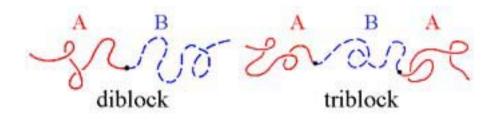
$$-(=(-)) + (=(-))$$

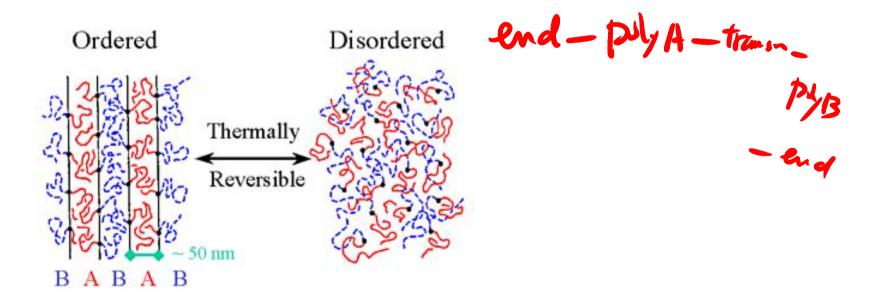
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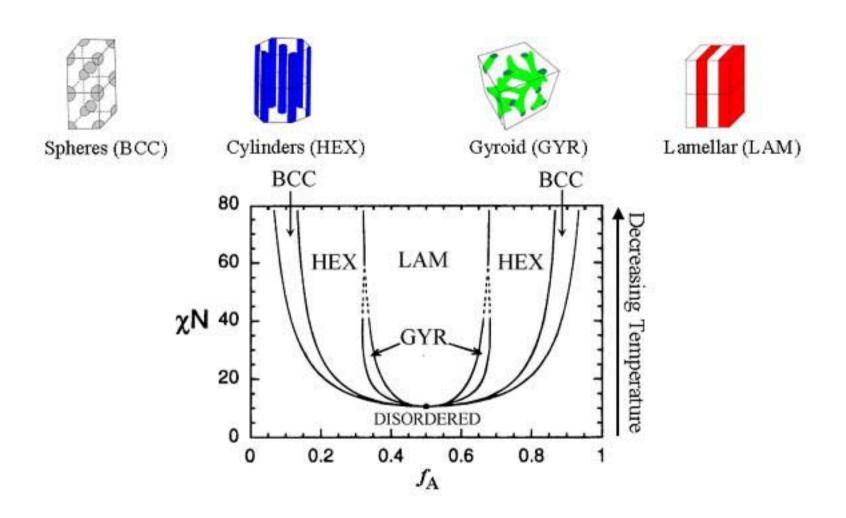
$$-(-)) + (=(-))$$

$$-(-)) + (=(-))$$









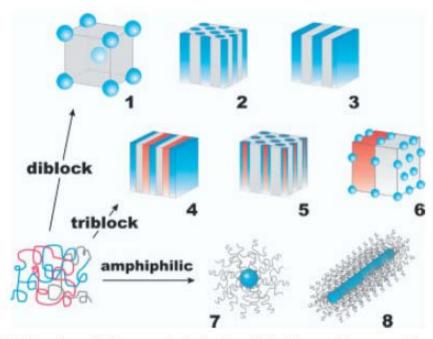
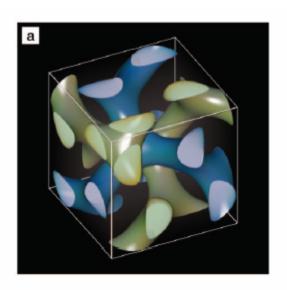
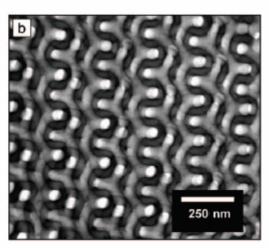


Fig. 1. Sketches of equilibrium morphologies from BC self-assembly, among the most frequently used for nanofabrication. For diblock copolymers in bulk: body-centered cubic-packed spheres (1), hexagonally ordered cylinders (2), lamellae (3). For triblock copolymers: lamellae (4), hexagonal coaxial cylinders (5), spheres between lamellae (6). For amphiphilic BCs in solution: spherical micelles (7), and cylindrical micelles (8). Periodicities, or micellar dimensions, are in the range 10–100 nm.

Block Copolymer as Photonic Materials



nign-cielectric material about a template



1.6:1) (Figure 20).--

However, it turns out that the double gyroid network structure does not possess

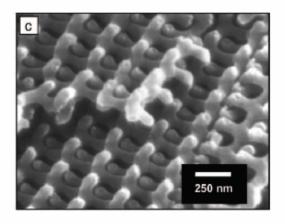
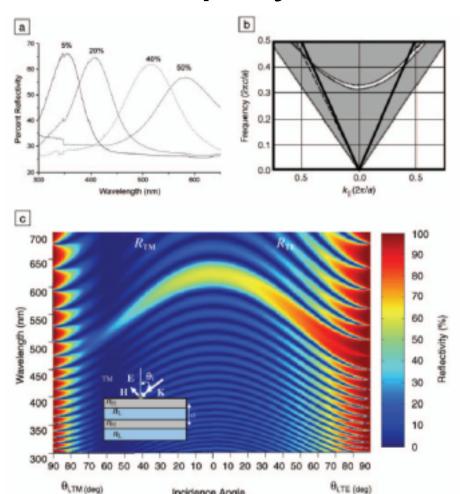


Figure 2. (a) Schematic illustration of the unit cell of the double gyroid morphology. The double gyroid structure comprises two interpenetrating three-dimensionally continuous networks of the minority component (shown in blue and yellow to help in visualization). (b) Transmission electron micrograph of an 80-nm-thick cryo-microtomed thin section of the 750 kg/mol PS-PI block copolymer. The image is of the [123] projection of the microstructure, yielding a lattice parameter of the cubic cell of 250 nm. The isoprene matrix has been stained with osmium tetroxide, leaving the styrene networks light in this bright-field micrograph. (Reprinted with permission from Reference 26.) (c) Scanning electron microscopy secondary electron image of the double gyroid styrene networks remaining after UV/ozone etching, showing that the networks remain intact and self-supporting after processing. The dimensions of the network structure are not perceptibly changed by the processing. (Reprinted with permission from Reference 26.)

Block Copolymer as Photonic Materials



Incidence Angle

Figure 1. (a) Reflectivity of ternary block copolymer (PS-PI with 194 kg/mol of PS block and 197kg/mol of PI block)/homopolymer (13kg/mol of PS and 13kg/mol of PI) blends containing 5%, 20%, 40%, and 50% added homopolymer, respectively. The progression of the stop band to longer wavelengths and broader peaks with increasing homopolymer content is evident. (Reprinted with permission from Reference 17.) (b) A band diagram (dimensionless frequency versus dimensionless wave vector) using the refractive indices of polystyrene (PS) and polyisoprene (PI) and the layer thicknesses of a PS-b-PVPS/PI blend (c is the speed of light in a vacuum, a is the lamellar domain periodicity). The transverse-electric (TE) polarization modes are on the right side, and the left side is for the transverse-magnetic (TM) polarized light. The shaded regions represent allowed propagating modes. The dotted curves are the band edges. The partial bandgap is the thin, crescent-shaped region between the second and third bands. The region between the solid black lines (the "light lines") defines the region of the diagram accessible to light incident from outside the material. The dashed curve on the left aide of the graph is the Brewster line, the angle where TM polarized light passes through the structure without reflection. (Reprinted with permission from Reference 16.) (c) Reflectivity plot constructed by the transfer matrix method for a 20-period stack of afternating PS and PI layers, where R_{th} and R_{th} represent the reflectivity for TM and TE polarization, respectively. Each layer is assumed to be 100 nm thick. The color represents the strength of the reflectivity at a particular frequency and angle of incidence. The inset shows a schematic of TM polarized light incident on the multilayer stack with an angle 6./E = electric field vector, H = magnetic field vector, k = wave vector, n_u = refractive index of high-index layer, n_i = refractive index of low-index layer, a = domain periodicity).

11.5.2 Dentritic Molecules

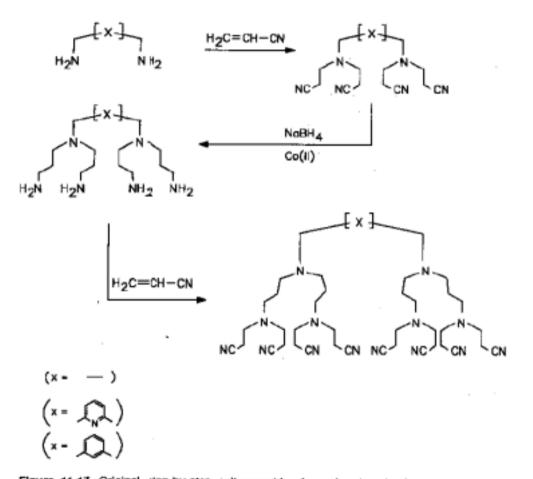


Figure 11.17. Original step-by-step self-assembly of a polyamine dendrimer by alternating between steps that rep-lace the hydrogens of amino groups by cyanide groups $[-NH_2 \Rightarrow -N(CN)_2]$, and then acid hydrogens to the cyanide nitrogens $[-CN \Rightarrow -CNH_2]$. [From E. Buhleier, W. Wehner, and F. Vögtle. Synthesis 155 (1978).]

5th Generation PAMAM

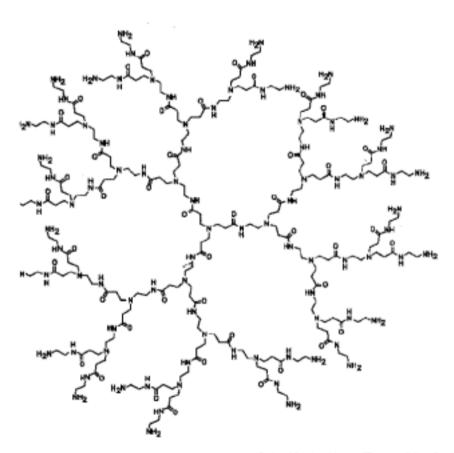


Figure 11.16. Fifth-generation polyaminoamine (PAMAM) dendrimer. [Prepared by D. A. Tomalia, H. Baker, J. R. Dewald, M. Hall, G. Kallos, S. Martin, J. Poeck, J. Ryder, and P. Smith, *Polym. J.* 17, 117 (1985).]

dendralysts

Figure 11.19. Dendrimer catalyst (dendralyst) with an Si core, and terminal group anyinickel complexes as the catalytically active functional groups. [From J. W. J. Knapen, A. W. van der Made, J. C. de Wilde, P. W. N. M. van Leeuwenn, P. Wijkens, D. M. Grove, and G. van Koton, *Nature* 372, 658 (1994).]

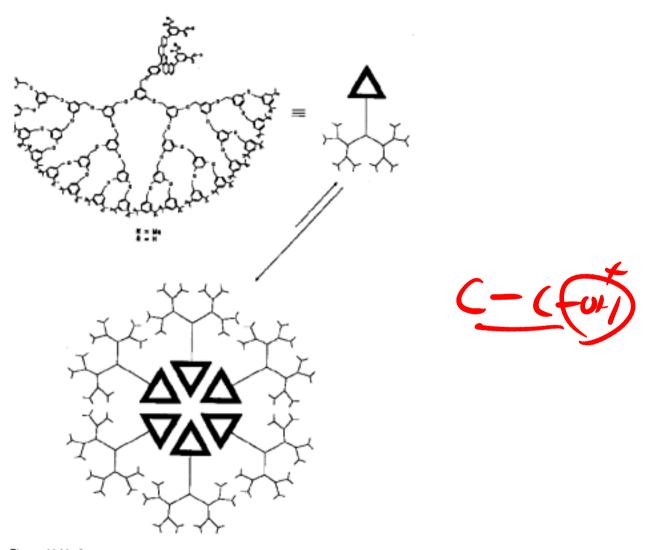


Figure 11.20. Sketch of sixfold (hexamer) supramolecular dendritic complex showing the structural formula of an individual component dendrimer at the upper left, the same component in a compact notation at the upper right, and the final self-assembled configuration of six components at the bottom. [Adapted from A. Archut and F. Vögtle, in Nalwa (2000), Vol. 5, Chapter 5, p. 367.]

Chapter 12

Biological Materials

12.2 Size of the biomaterials

DNA.
$$\phi = 2 \text{ nm}$$
, unit = 0.34 nm
ammodum unit ~ 0.42 nm
 $d = 0.1184 \left(\frac{Mw}{p}\right)^{1/3}$
 $1.6 \Rightarrow d = 0.12 \left(\frac{Mw}{s}\right)^{1/3}$
1.3 $68 \text{ kD} \rightarrow d \sim 5 \text{ nm}$

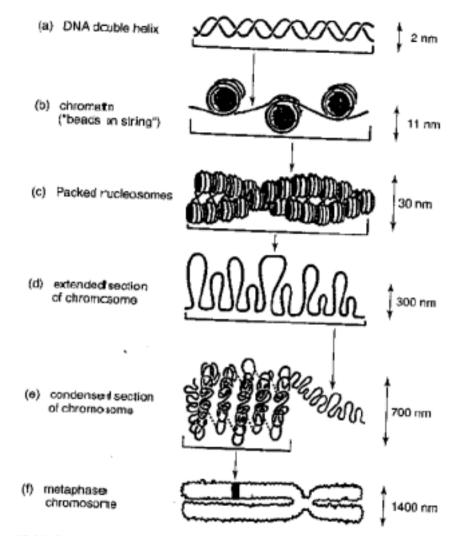
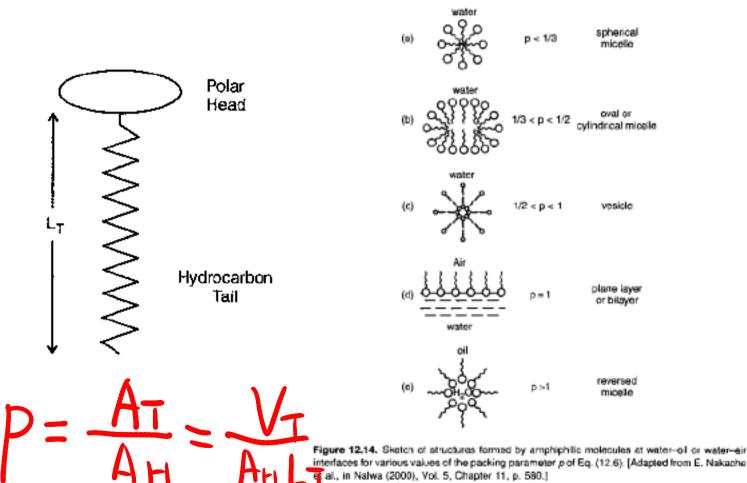


Figure 12.11. Successive twistings and foldings during the packing of DNA into mammalian chromosomes, with the sizes at successive stages given in nanometers. [From R. J. Nossal and H. Lecar, *Molecular and Cell Biophysics*, Addison-Wesley, Boston, 1991, Fig. 4.9 (p. 118).]

12.4.2 Micelles and Vesicles



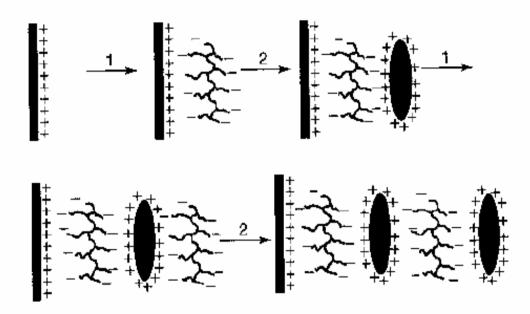


Figure 12.16. Sketch of the sequential adsorption process for the formation of a polyion film. The upper figure shows a positively charged substrate (left) that has adsorbed a negatively charged polyelectrolyte by being dipped into a negative electrolyte solution (center), and then adsorbed a positively charged layer from a positive electrolyte solution (right). The lower figure shows two additional steps in the sequential adsorption process. [From T. M. Cooper, in Nalwa (2000), Vol. 5, Chapter 13, p. 720.]